

Welcome to the 16th Annual Meeting of the SRC/Sematech

Engineering Research Center for Environmentally Benign Semiconductor Manufacturing

March 20-22, 2012

ERC: A Pioneer

in University-Industry Collaborative Research on the ESH Aspects of SC Manufacturing

Founding Universities (1996)

- > U Arizona
- > U California Berkeley
- > MIT
- > Stanford

16 years of Experience

Other University members

- Arizona State U (1998)
- Columbia (2006 2009)
- Cornell (1998)
- Georgia Inst. of Tech. (2009)
- U Maryland (1999-2003)
- U Massachusetts (2006 2009)
- U North Carolina (2009)
- Purdue (2003 2008)
- U Texas Dallas (2009)
- Tufts (2005 2008)
- U Washington (2008-)
- U Wisconsin (2009-)
- UCLA (2011)
- North Carolina A&T (2012)
- Johns Hopkins (2012)
- Colorado School of Mines (2012)

Welcome to

The New University Partners

- Colorado School of Mines
- > Johns Hopkins University
- North Carolina State A&T
- > UCLA

> U North Carolina/Greensboro

Sources of Funding

- SRC (core)
- Sematech (core)
- Industrial members (membership)
- **Customized projects** (including Intel/ERC new HVnM initiative, Sematech and SRC customized projects, etc)
- Cost sharing by participating universities
- Grants from Federal and State agencies (NSF, SFAz, WSP, etc.)
- **Donations** (Koshiyama Planarization Chair by Fujimi; Simon Karecki memorial Endowment; Ella Philipossian memorial endowment, etc.)

Success in creating research leverage for S/C industry

Types of ERC Research Projects

- > Two types of projects:
 - <u>Core projects</u> (mainly funded by the core ERC contract; cost shared by other ERC funds)
 - <u>Customized projects</u> (non-core funding)
- Core projects were selected through RFP process, proposals, and review/selection by a panel appointed by SRC.
- Customized projects are added throughout the year.
 Review and selection procedures are set by the ERC and the sponsors.

ERC Thrust Areas

Environmentally Sustainable IC Manufacturing

Thrust AThrust BThrust CNovelESH-FriendlyESH AspectsSolutionsNovelof Futureto ExistingMaterials andNano-ScaleESH ProblemsProcessesManufacturing

Enabling ESH Fundamentals

<u>Core Project in (2009 – 2012)</u>

A) ESH Challenges of Existing Processes (4 Universities)

 Lowering the Environmental Impact of High-k and Metal Gate-Stack Surface Preparation Processes
 PIs: Yoshio Nishi (Stanford); Srini Raghavan, Farhang Shadman (U of Arizona); Bert Vermeire (Arizona State U)

Fundamentals of Advanced Planarization: Pad Micro-Texture, Pad Conditioning, Slurry Flow, and Retaining Ring Geometry PIs: Ara Philipossian (U of Arizona); Duane Boning (MIT)

<u>Core Project in (2009 – 2012)</u>

B) ESH-Friendly Novel Materials and Process (3 Universities)

- Low-ESH-impact Gate Stack Fabrication by Selective Surface Chemistry PI: Anthony Muscat (U of Arizona)
- Carbon Dioxide Compatible Additives: Design, Synthesis, and Application of an Environmentally Friendly Development Process to Next Generation Lithography PIs: Christopher Ober (Cornell); Juan de Pablo (U of Wisconsin)
- Improvement of ESH Impact of Back-End-of-Line (BEOL) Cleaning Formulations Using Ionic Liquids to Replace Traditional Solvents *PI: Srini Raghavan (U of Arizona)*
- > High-Dose Implant Resist Stripping (HDIS): Alternatives to ASH/Strip Method PI: Srini Raghavan (U of Arizona)
- Sugar-Based Photoacid Generators (Sweet PAGs): Environmentally Friendly Materials for Next Generation Photolithography PIs: Christopher Ober (Cornell); Reyes Sierra (U of Arizona)

<u>Core Project in (2009 – 2012)</u>

C) ESH Aspects of Nano-Materials (6 Universities)

- Development of Quantitative Structure-Activity Relationship for Prediction of Biological Effects of Nanoparticles Associated with Semiconductor Industries PIs: Yongsheng Chen (Georgia Inst. of Technology), Trevor Thornton, Jonathan Posner (Arizona State U)
- Environmental Safety and Health (ESH) Impacts of Emerging Nanoparticles and Byproducts from Semiconductor Manufacturing
 PIs: Jim Field, Reyes Sierra, Scott Boitano, Farhang Shadman (U of Arizona); Buddy Ratner (U of Washington)
- Computational Models and High-Throughput Cellular-Based Toxicity Assays for Predictive Nanotoxicology PIs: Alex Tropsha, Russell Mumper (U of North Carolina)
- Predicting, Testing, and Neutralizing Nanoparticle Toxicity
 PIs: Steven Nielsen, Rockford Draper, Paul Pantano, Inga Musselman, Gregg
 Dierkmann, (U of Texas- Dallas); Ara Philipossian (U of Arizona)

New Projects (2012- 2015)

A) ESH Challenges of Existing Processes

- ESH-Friendly Cleaning and Rinsing of Multi-Material Surfaces and Structures: Srini Raghavan, Manish Keswani, and Farhang Shadman (U Arizona)
- Cell-based Toxicity Assay-on-Chip for the Next-Generation CMOS
 Technology: Shyam Aravamudhan and Shanthi Iyer (North Carolina State A&T);
 Adam Hall and Ethan Taylor (U North Carolina/Greensboro)



B) ESH-Friendly Novel Materials and Process

- Non-PFC Plasma Chemistries for Patterning Complex Materials and Structures: Jane Chang (UCLA)
- Pad-in-a-Bottle: Planarization with Slurries Containing Suspended Polyurethane Beads: Ara Philipossian (UA) and Duane Boning (MIT)

New Projects (2012 - 2015)

C) ESH Aspects of Nano-Materials

- Interactions of Chemical Mechanical Planarization Nanoparticles with Model Cell Membranes: Implications for Nanoparticle Toxicity: Kai Loon Chen (Johns Hopkins)
- Dispersion, Bioaccumulation, and Mechanisms of Nanoparticle (NP) Toxicity: Steven Nielsen, Rockford Draper, Paul Pantano, Inga Musselman, and Gregg Dieckmann (U Texas/Dallas)
- Computer-Aided Design of Nanomaterials with the Desired Bioactivity and Safety Profiles: Alex Tropsha, and Denis Fourches (U North Carolian/Chapel Hill)
- Detection of Engineered Nanomaterials at Semi-Conductor Facilities and Consumer Products: Paul Westerhoff and Pierre Herckes (Arizona State U); Jonathan Posner (U. Washington); James Ranville, and Chris Higgins (Colorado School of Mines)

New Faculty Co-PIs

- Arizona State University
 - **Paul Westerhoff** (Civil and Environmental Engineering)
 - Pierre Herckes (Chemistry and Biochemistry)
- Colorado School of Mines
 - Chris Higgins (Environmental Science and Engineering)
 - o James Ranville (Chemistry and Geochemistry)
- Johns Hopkins University
 - Kai Loon Chen (Geography and Environmental Engineering)
- North Carolina State A&T
 - o Shyam Aravamudhan (Nanoscience and Nanoengineering)
 - Shanthi Iyer (Electrical and Computer Engineering)
- University of California/ Los Angeles
 - o Jane Chang (Chemical Engineering)
- University of North Carolina/Greensboro
 - o Adam Hall (Nanosciences)
 - o Ethan Taylor (Chemistry and Biochemistry)
- > University of Washington
 - o Jonathan Posner (Mechanical Engineering, Chemical Engineering)

AGENDA

2012 SRC/SEMATECH ERC REVIEW MEETING Wednesday, March 21st

7:00 – 7:45 AM	Continental Breakfast and Registration [Pima/Sabino Foyer]
7:30 – 7:50 AM	TAB/PAG Caucus [Ventana Room]
7:50 – 8:15 AM	Introduction and Overview: Farhang Shadman [Pima/Sabino]
8:15 – 8:35 AM	Improvement of ESH Impact of Back End of Line (BEOL) Cleaning Formulations Using Ionic Liquids to Replace Traditional Solvents (425.034) Srini Raghavan (UA)
8:35 – 8:55 AM	Development of an All-Wet Benign Process Based on Catalyzed Hydrogen Peroxide (CHP) Chemical System for Stripping of Implanted State-of-the-Art Deep UV Resists (425.033) Srini Raghavan (UA)
8:55 – 9:35 AM	Fundamentals of Advanced Planarization: Pad Micro-Texture, Pad Conditioning Slurry Flow, and Retaining Ring Geometry (425.032) Ara Philipossian (UA); Duane Boning (MIT)
9:35 – 9:50 AM	Break [Pima/SabinoFoyer]

9:50 – 10:15 AM	Supercritical Carbon Dioxide Compatible Additives: Design, Synthesis, and Application of an Environmentally Friendly Development Process to Next Generation Lithography (425.030 and 425.031) Chris Ober (Cornell); Juan dePablo (U. Wisconsin)
10:15 – 10:40 AM	Sugar-Based Photoacid Generators (Sweet PAGs): Environmentally Friendly Materials for Next Generation Photolithography (425.029) Chris Ober (Cornell); Reyes Sierra (UA)
10:40 – 11:00 AM	Low-ESH-Impact Gate Stack Fabrication by Selective Surface Chemistry (425.026) Anthony Muscat (UA)
11:00 - 11:30 AM	* Introduction: Projects on ESH Aspects of Nano-Materials, Jim Field (UA) Environmental Safety and Health (ESH) Impacts of Emerging Nanoparticles and Byproducts from Semiconductor Manufacturing (425.023 and 425.024) Jim Field, Scott Boitano, Reyes Sierra, Farhang Shadman (UA); Buddy Ratner (U. Washington)
11:30 AM -1:00PM	Lunch [Canyon Rooms]
1:00 – 1:25 PM	Development of Quantitative Structure-Activity Relationship for Prediction of Biological Effects of Nanoparticles Associated with Semiconductor Industries (425.025) Yongsheng Chen (Georgia Tech); Jonathan Posner, Trevor Thornton (ASU)

1:25 – 1:50 PM	Predicting, Testing, and Neutralizing Nanoparticle Toxicity (425.027) Steven Nielsen, Rockford Draper, Paul Pantano, Inga Musselman, Gregg Dieckmann (UT-Dallas)
1:50 – 2:15 PM	High-Throughput Cellular-Based Toxicity Assays for Manufactured Nanoparticles and Nanostructure-Toxicity Relationship Models (425.035) Alex Tropsha (UNC-Chapel Hill)
2:15 – 2:30 PM	*Summary of Results and Conclusions of Four Nano-Tox Projects Jim Field (UA)
2:30 – 2:40 PM	Break [Pima/Sabino Foyer]
2:40 – 2:55 PM	Lowering the Environmental Impact of High-k and Metal Gate-Stack Surface Preparation Processes (425.028) Yoshio Nishi (Stanford); Srini Raghavan, Farhang Shadman (UA); Bert Vermeire (ASU)
2:55 – 3:15 PM	<u>Customized Projects</u> Novel Methods for Reducing UHP Gas Usage in Fabs: Back Diffusion Minimization Roy Dittler (UA)
	Other Customized Projects
3:15 – 3:30 PM	General Discussion

3:30 – 3:45 PM	Simon Karecki Award Presentation
3:45 – Open	Poster Session [Madera Room]
4:30 – 5:15 PM	SRC Student/Industry Networking Event [Madera/Pima Rooms]
4:30 – Open	Hors d'oeuvres [Madera/Pima Rooms]
5:00 – Open	Cash bar [Madera/Pima Rooms]
5:15 – 7:45 PM	TAB/PAG Caucus w/ working dinner [Sabino Room]
5:30 – Open	Buffet Dinner [Canyon Foyer & Canyon Rooms]
7:00 – Open	Special HVnM Planning Meeting [Ventana Room]
7:00 – Open	Meetings of Research Groups [Canyon Rooms]

Thursday, March 22nd

6:30 – 7:30 AM	Continental Breakfast [Pima/Sabino Foyer]
7:30 – 7:35 AM	Dean's Message: Jeff Goldberg, Dean of Engineering, UA
7:35 – 7:50 AM	Update on new proposals and initiatives Intel/ERC High-Volume Nano-Manufacturing Initiative Other Initiatives
7:50 – 10:00 AM 7:50 – 8:00	<u>Presentation of New Projects</u> : 425.037: <i>Cell-based Toxicity Assay-on-Chip for the Next-Generation CMOS</i> <i>Technology</i> <u>Shyam Aravamudhan</u> , Shanthi Iyer (NC A&T); Adam Hall, Ethan Taylor (UNC/Greensboro)
8:00 - 8:20	425.038: Non-PFC Plasma Chemistries for Patterning Complex Materials and Structures <u>Jane Chang</u> (UCLA)
8:20 - 8:30	425.039: 'Pad-in-a-Bottle': Planarization with Slurries Containing Suspended Polyurethane Beads <u>Ara Philipossian (UA); Duane Boning,</u> MIT)
8:30 - 8:40	425.040: Detection of Engineered Nanomaterials at Semi-Conductor Facilities and Consumer Products (<u>Paul Westerhoff</u> , Pierre Herckes (ASU); Jonathan Posner (U.Washington); James Ranville, Chris Higgins (Colorado School of Mines)
8:40 - 8:55 AM	Break [Pima/Sabino Fover]

8:55 – 9:05	425.041: Interactions of Chemical Mechanical Planarization Nanoparticles with Model Cell Membranes: Implications for Nanoparticle Toxicity (<u>Peng Yi</u> , Kai Loon Chen (Johns Hopkins)
9:05 – 9:15	425.042: Dispersion, Bioaccumulation, and Mechanisms of Nanoparticle (NP) Toxicity (<u>Steven Nielsen</u> , Rockford Draper, Paul Pantano, Inga Musselman, Gregg Dieckmann (UT/Dallas)
9:15 – 9:25	425.043: ESH-Friendly Cleaning and Rinsing of Multi-Material Surfaces and Structures (Srini Raghavan, Farhang Shadman, Manish Keswani (UA)
9:25 – 9:35	425.044: Computer-Aided Design of Nanomaterials with the Desired Bioactivity and Safety Profiles (<u>Alex Tropsha,</u> Denis Fourches (UNC/Chapel Hill)
9:35 – 10:00 AM	Q/A and Comments on New Projects
10:00 - 11:20 AM	IAB Meeting [Ventana]
10:00 - 11:00 AM	Meeting of Research Groups [Canyon]
11:00 - 11:20 AM	ISMI Program on ESH (His-An Kwong, ISMI) [Pima/Sabino]
11:20 – 12:00 AM	Feedback to PIs [Pima/Sabino]
12:00 – 2:00 PM	Buffet Lunch [Pima/Sabino Foyer & Canyon Rooms]
12:30 – 2:00 PM	Executive Advisory Board Meeting [Board Room]
2:00 PM	Program End